



VACUUM PLANT FOR FILM DEPOSITION BY ELECTRON-BEAM EVAPORATION

ELU TM 38

Purpose:

Deposition of mono- and multilayer thin films onto substrates (plates) by electron-beam evaporation of materials including film coating normally to substrate surface.

Special characteristics:

- Group processing of $\varnothing 76$ or $\varnothing 100$ mm substrates;
- Lock-chamber for loading and unloading substrates;
- Rotary domical substrate holder;
- 4-crucible electron-beam evaporator.
- Preliminary substrate heating and cleaning by ion source in lock-chamber;
- Oil-free (dry) pumping system (forevacuum and 2 cryogenic pumps);
- Microprocessing control system;
- Consumed power not more than 20 kW;
- 4 m² area per one plant.

